

IN THE CLAIMS

1 - 15. (Canceled)

16. (Previously Presented) A method of manufacturing an electron source comprising steps of:

- exposing a surface of a substrate to a sealed atmosphere, on which a plurality of electron-emitting devices are to be formed; and
- introducing a gas containing carbon into the sealed atmosphere, wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step, and
- wherein the introducing of a gas containing carbon is performed while exhausting the sealed atmosphere formed by the chamber.

17. (Previously Presented) A method of manufacturing an electron source comprising steps of:

- exposing a surface of a substrate to a sealed atmosphere, on which a plurality of electron-emitting devices are to be formed; and
- introducing a gas containing carbon into the sealed atmosphere, wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step, to reduce moisture absorbed to a surface of the chamber, and

wherein the introducing of a gas containing carbon is performed while exhausting the sealed atmosphere formed by the chamber.

18. (Previously Presented) A method of manufacturing an electron source comprising steps of:

exposing a surface of a substrate to a sealed atmosphere, wherein an electron-emitting region to be formed is disposed on the surface of the substrate; and

introducing a gas containing carbon into the sealed atmosphere,

wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step, and

wherein the introducing of a gas containing carbon is performed while exhausting the sealed atmosphere formed by the chamber.

19. (Previously Presented) The method according to Claim 18, further comprising the step of applying a voltage to an electro-conductive member, the electroconductive member being disposed on the surface of the substrate.

20. (Previously Presented) A method of manufacturing an electron source comprising steps of:

exposing a surface of a substrate to a sealed atmosphere, wherein an electro-conductive member, in which an electron-emitting region is to be formed, is disposed on the surface of the substrate; and

introducing a gas containing carbon into the sealed atmosphere, wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step, to reduce moisture absorbed to a surface of the chamber, and

wherein the introducing of a gas containing carbon is performed while exhausting the sealed atmosphere formed by the chamber.

21. (Previously Presented) The method according to Claim 20, further comprising the step of applying a voltage to the electro-conductive member.

22. (Previously Presented) A method of manufacturing an electron source comprising steps of:

exposing a surface of a substrate to a sealed atmosphere, wherein an electro-conductive member, capable of being subjected to an activation of an electron-emitting function, is disposed on the surface of the substrate; and

introducing a gas containing carbon into the sealed atmosphere, wherein the sealed atmosphere is formed by a chamber and the chamber is heated before said introducing step, and

wherein the introducing of a gas containing carbon is performed while exhausting the sealed atmosphere formed by the chamber.

23. (Previously Presented) The method according to Claim 22, further comprising the step of applying a voltage to the electro-conductive member.

24. and 25. (Canceled)